

†Electronic Supplementary Information (ESI) for Nanoscale

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Supporting information for

Investigation of surface passivation mechanism through Ag-doped Al-rich film using solution processes

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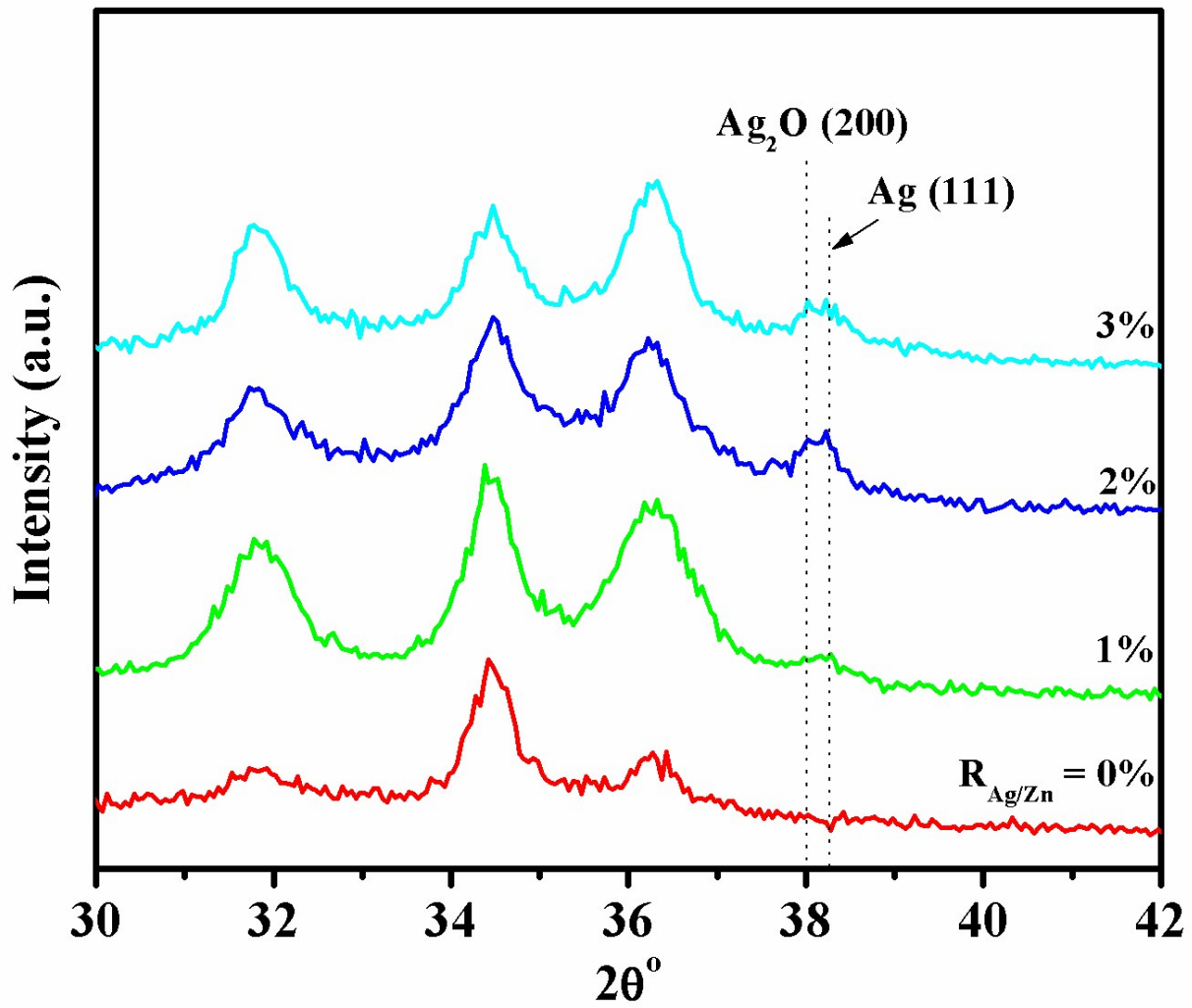


Figure S1. XRD spectra of ZnO:Al:Ag film in 2θ range of 30 to 42° coated on n-Si and annealed in forming gas.

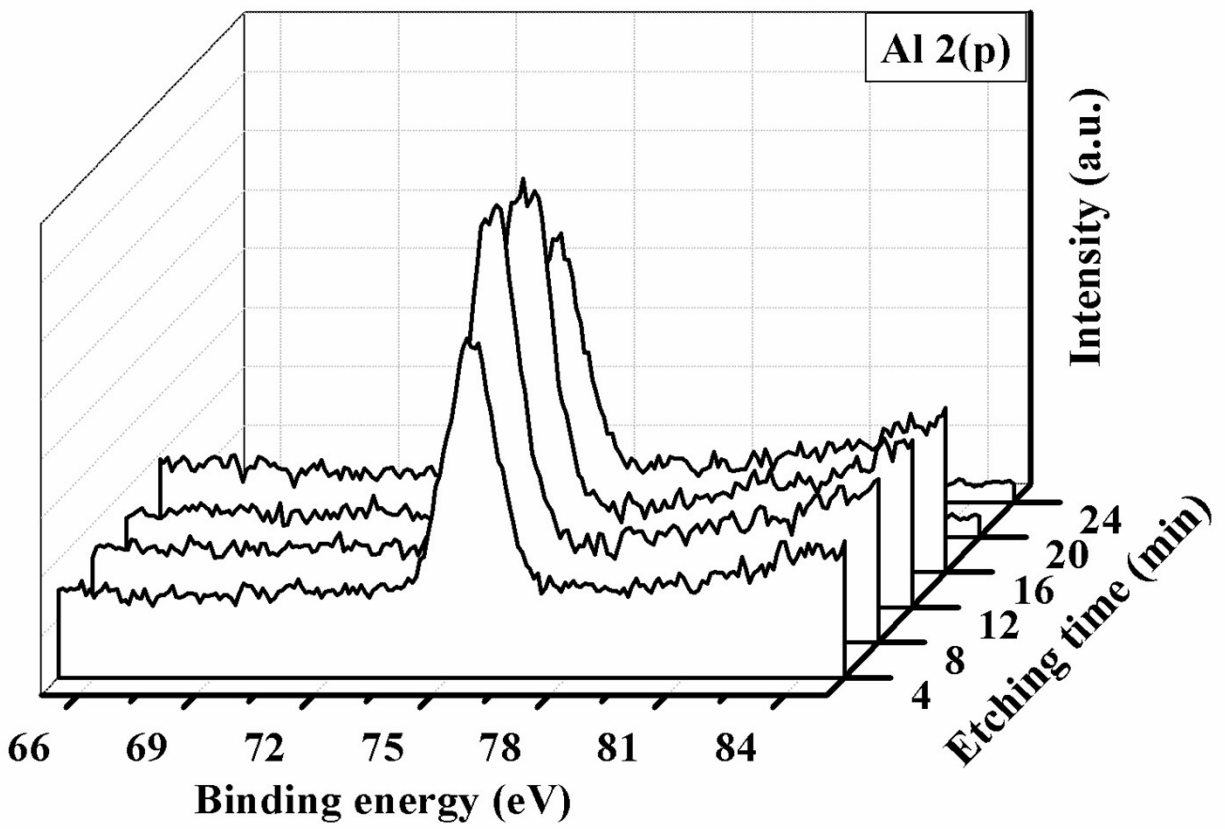


Figure S2. XPS spectra of a montage display of Al 2p with etching time.

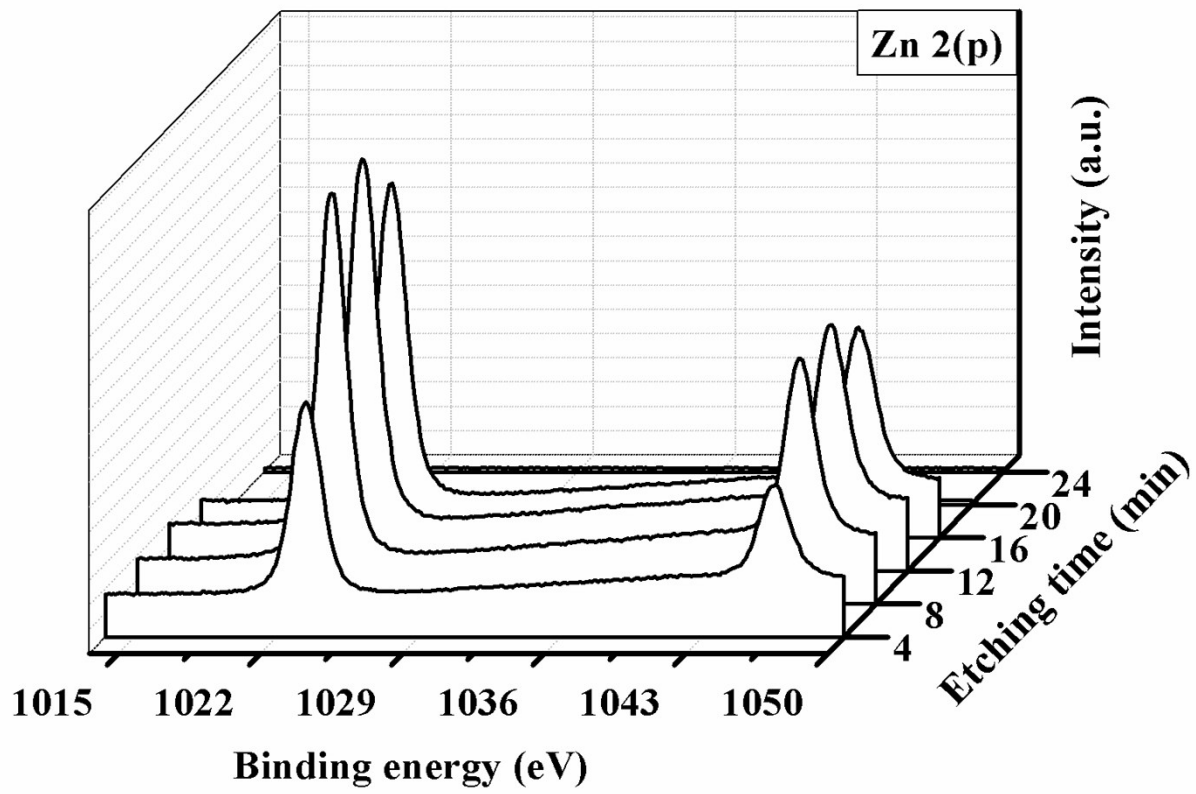


Figure S3. XPS spectra of a montage display of Zn 2p with etching time.

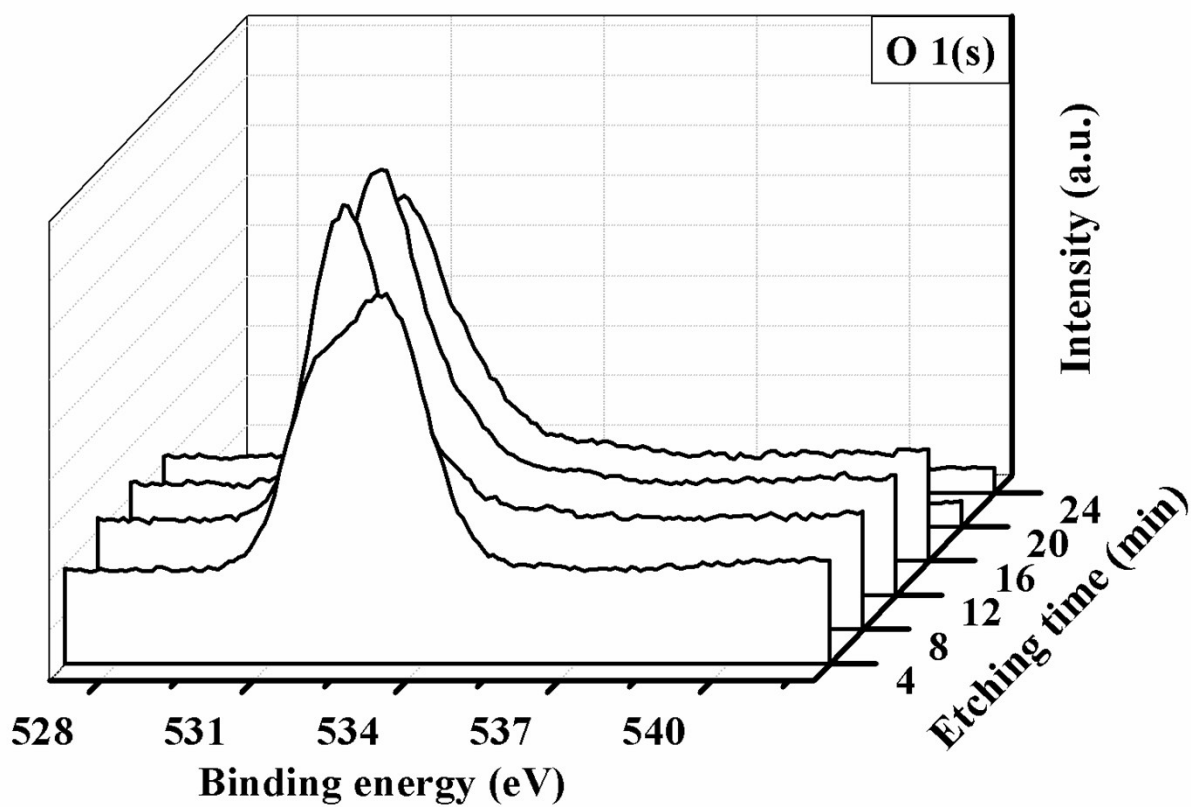


Figure S4. XPS spectra of a montage display of O 1s with etching time.

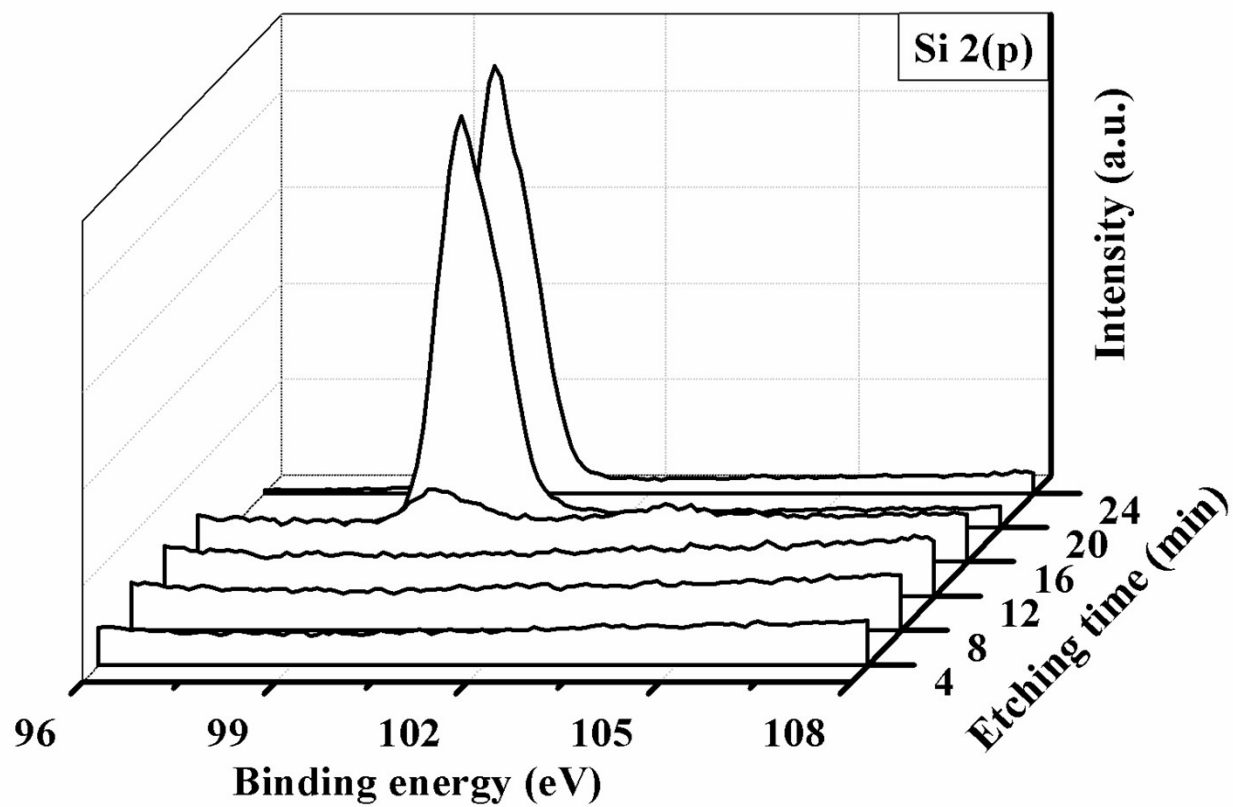


Figure S5. XPS spectra of a montage display of Si 2p with etching time.

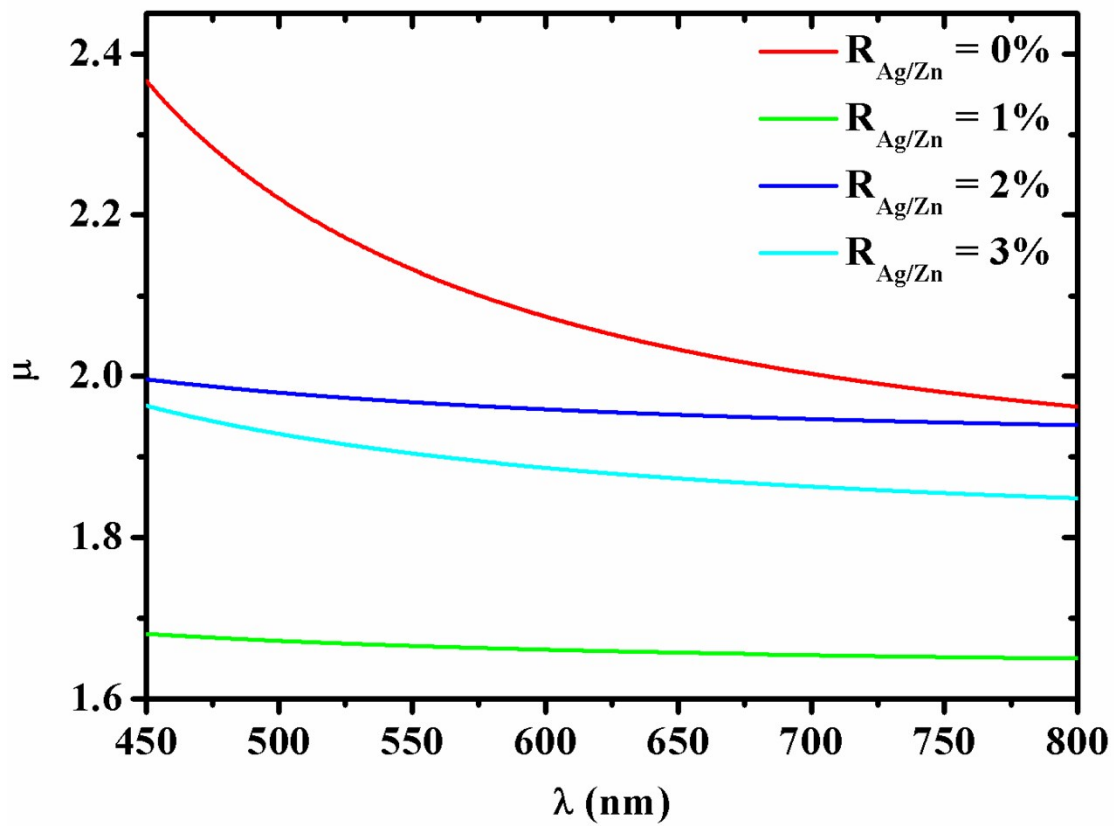


Figure S6. Refractive index of ZnO:Al:Ag films coated on polished Si.

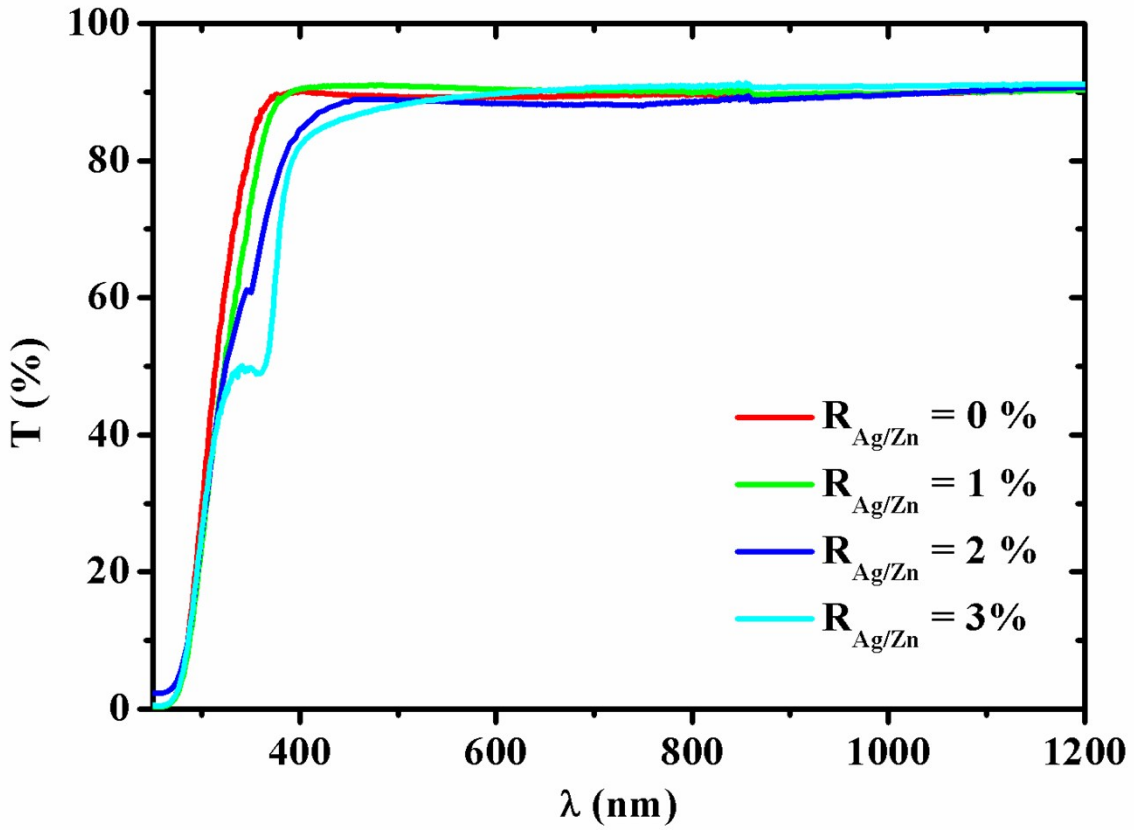


Figure S7. Transmittance spectra of ZnO:Al:Ag films coated on glass for various $R_{Ag/Zn}$.